

Circuit Considerations for Spin-Switched MRAM Devices

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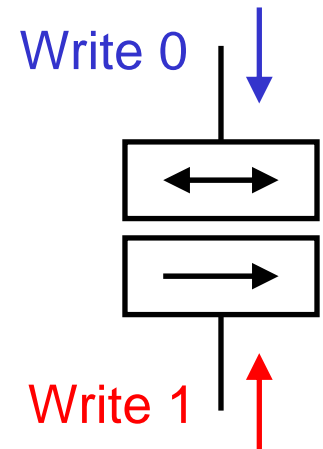
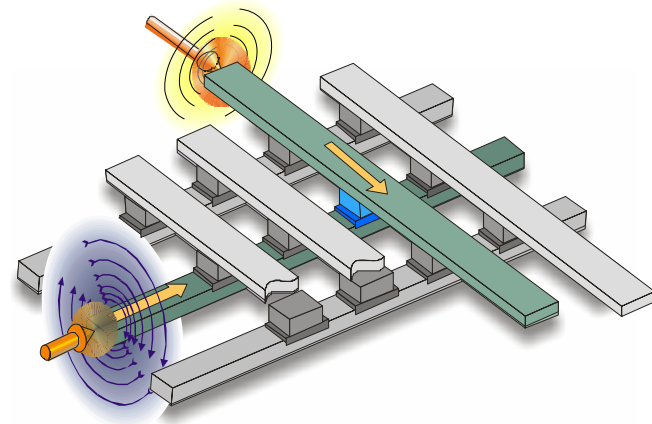
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Outline

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- Current state of MRAM
- Potential advantages of spin-switching
- Spin-switched MTJ current-voltage characteristic
- Sensing considerations
- 1T1MTJ array architecture
- 2T1MTJ array architecture
- Cross-point array architecture
- Summary

Introduction

- Conventional MRAM written by magnetic fields
 - Generated by currents passing across cell
 - Read / write mechanisms relatively distinct
- Spin-switched MRAM written by spin-transfer
 - Achieved by tunneling current through MTJ
 - Read / write coupled - both use tunneling current
 - Potential advantages but new design challenges
- What array architecture & device characteristics are required?
 - To make spin-switched MRAM an attractive option



Current State of MRAM

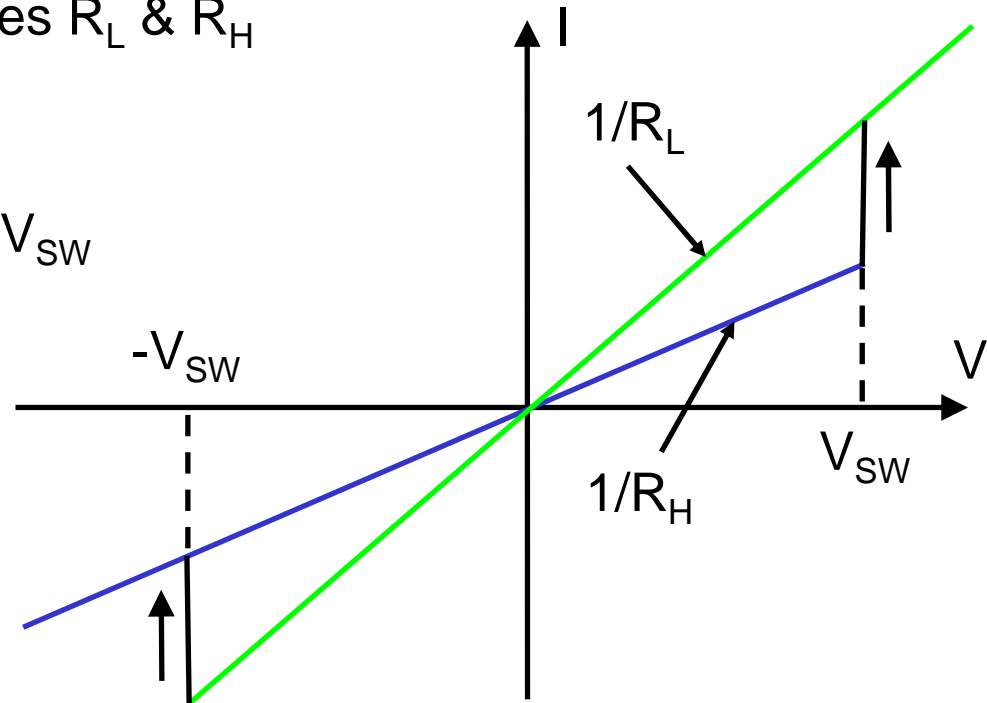
- Density - cell area $\sim 1.5\lambda m^2$ in $0.18\lambda m$ technology [1,2]
- Performance - read access/cycle, write cycle $\sim 20-40ns$
- Power
 - Data retention, standby - excellent
 - Read active - competitive with other memories
 - Write active - relatively high, dominated by write currents
- Process adder
 - $\sim 3-5$ masks & changes to 2 metal levels
- Device parameters
 - $R_{MTJ} \sim 10K\Omega$, MR $\sim 20-40\%$ at $V_{MTJ} \sim 250mV$
 - Write currents $\sim 1-10mA$ for $\sim 5-10ns$

Potential Advantages of Spin-Switching

- Lower active write current / power
 - Power dissipated in cell vs. along BL / WL
- Improved write margin
 - Ability to write selected cell without disturbing others
 - Eliminate BL / WL half select, adjacent BL / WL coupling effects
- Reduced process adder
 - ~ 1-2 masks with no changes to metal levels
- Improved density
 - Eliminate adjacent contact - can contact from below
 - Larger arrays - currently limited by BL / WL IR drops
- Scalability?
 - How do MTJ size & write current scale, incl. thermal SER effects?

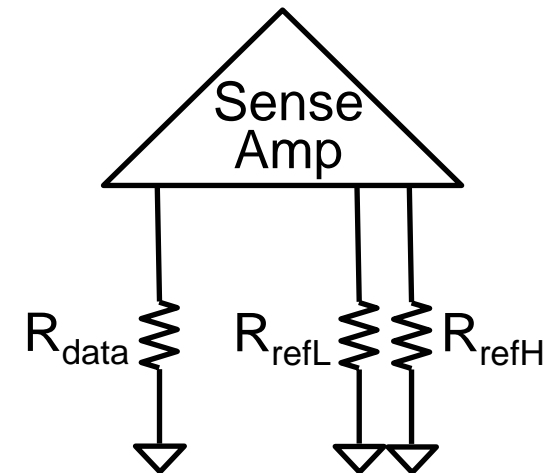
Spin-Switched MTJ Current-Voltage Characteristic

- Ideally
 - Two linear resistance states R_L & R_H
 - $R_H = R_L \times (1 + MR)$
 - Hysteretic switching at $\pm V_{SW}$
- In reality, probably
 - Non-linear
 - Non-constant MR
 - Non-symmetric
- Some of these non-idealities may be good
- $V_{SW} > V_{RD}$ with margin to prevent read disturbs



Sensing Considerations

- Assume data, reference sensed concurrently - simplest, fastest (<~50ns)
 - Apply V , measure I
 - Reference = average of L & H reference cells
 - Relative signal = $I_{\text{SIGNAL}} / I_{\text{REF}} = MR / (MR + 2) \sim MR / 2$
- Must consider local matching of MTJs & FETs
 - ρ of $\Delta R_{\text{MTJ}} / R_{\text{MTJ}} \sim 1\%$
 - ρ of $\Delta I_{\text{DS}} / I_{\text{DS}} \sim 1\%$
 - ρ of $\Delta V_{\text{T}} \sim 1\text{mV}$
- Yieldable multi-Mb design requires
 - $MR / 2 > \sim 4\rho$ of $\Delta R_{\text{MTJ}} / R_{\text{MTJ}} \rightarrow MR > \sim 8\%$
 - $MR / 2 > \sim 3\rho$ of $\Delta I_{\text{DS}} / I_{\text{DS}} \rightarrow MR > \sim 6\%$
 - $MR / 2 > \sim 3\rho$ of $\Delta V_{\text{T}} / V_{\text{RD}} \rightarrow MR > \sim 6\%$ if $V_{\text{RD}} \sim 100\text{mV}$
- $MR > \sim 10\%$, $V_{\text{RD}} > \sim 100\text{mV}$ plus margin



1T1MTJ Array Architecture

- Operation

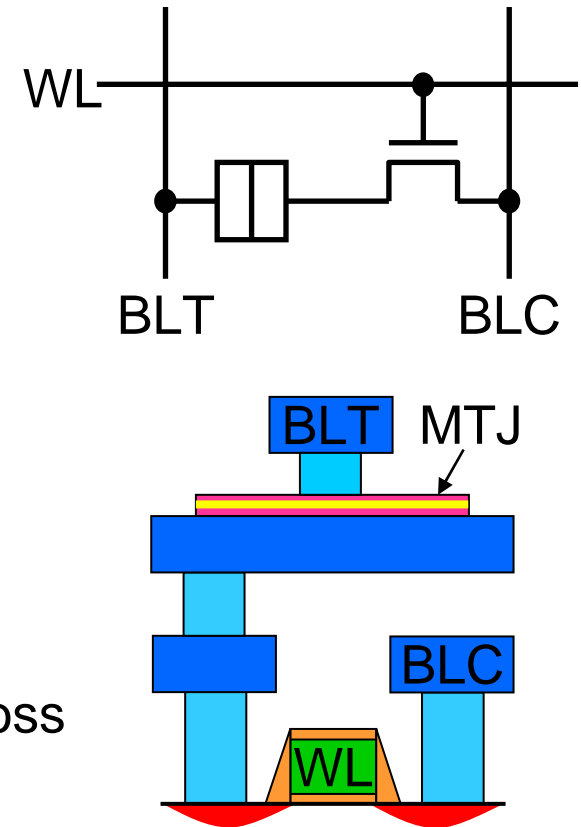
- Read: $WL = V_{DD}$, $BLT/C = V_{RD} / GND$
- Write 1: $WL = V_{DD}$, $BLT/C = V_{DD} / GND$
- Write 0: $WL = V_{DD}$, $BLT/C = GND / V_{DD}$

- Read

- Similar to conventional MRAM
- $R_{MTJ} \gg R_{FET}$ ($\sim 1K\Omega$) to avoid effective MR loss

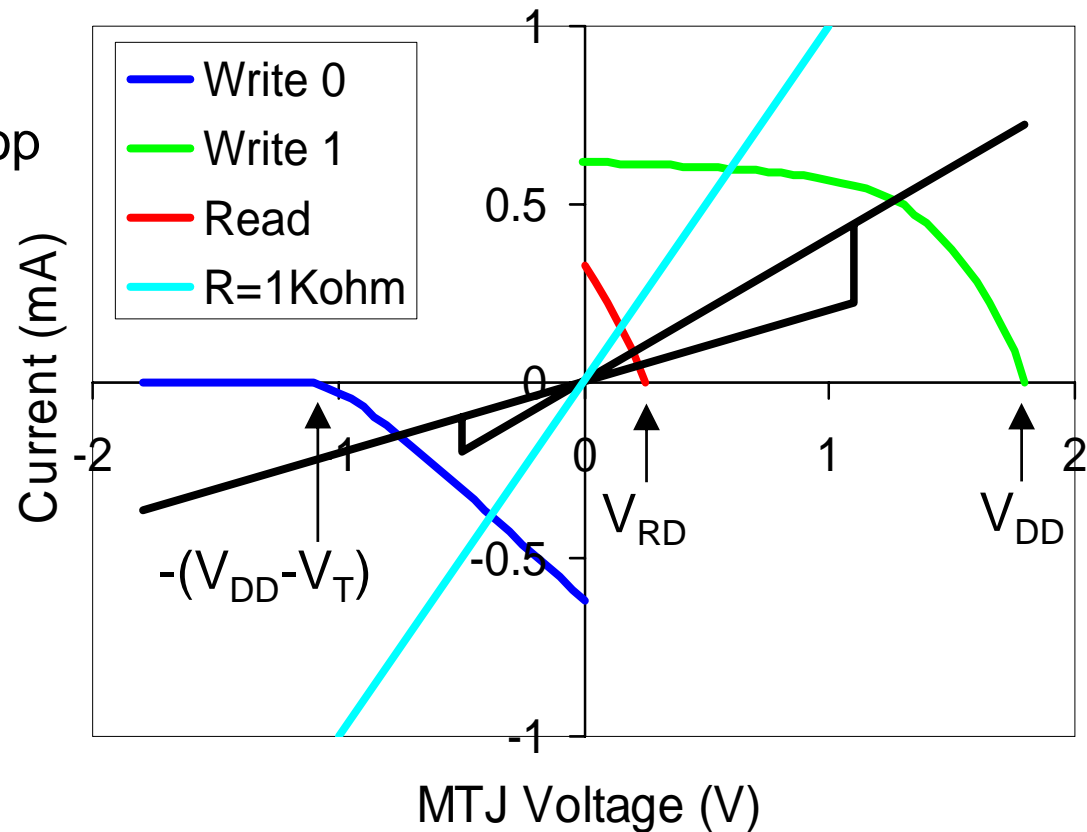
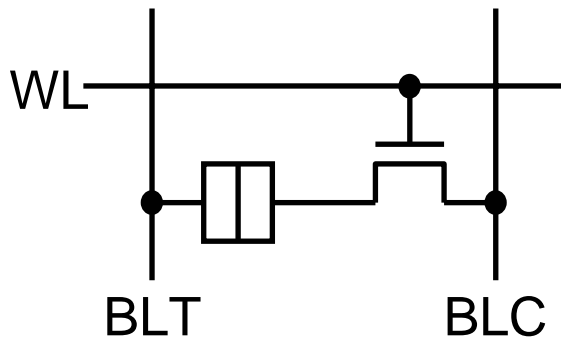
- Write

- Unlike conventional MRAM, write current limited by cell FET
- Particularly in Write 0 - FET turns off at $V_{MTJ} = V_{DD} - V_T$



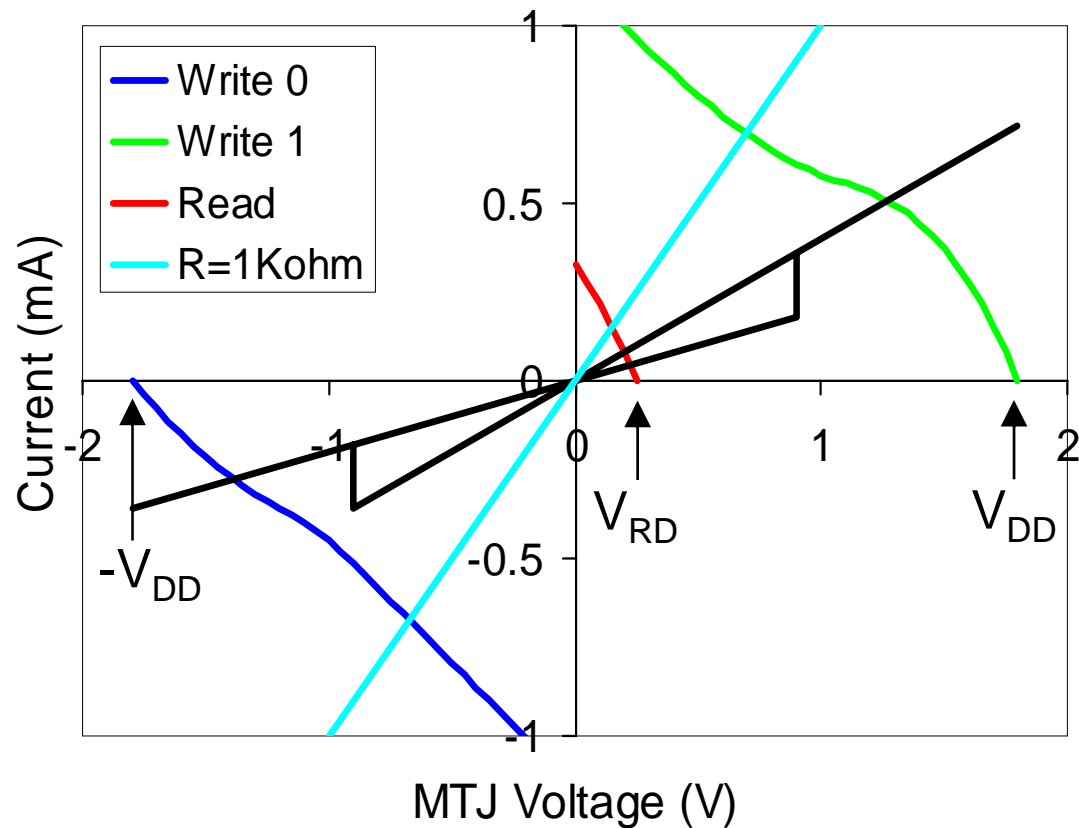
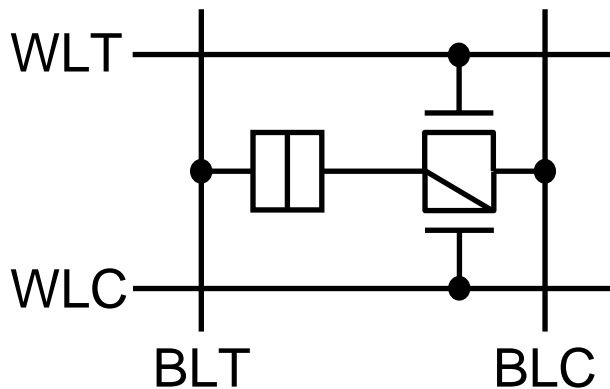
1T1MTJ Array Architecture (continued)

- FET load lines shown - $W/L = 1.0\lambda\text{m}/0.18\lambda\text{m}$, $V_{DD} = 1.8\text{V}$, $V_{RD} = 0.25\text{V}$
- MTJ hysteresis loop must fit inside write load lines with margin
- $V_{SW1} < V_{DD}$, $V_{SW0} < V_{DD} - V_T$, $I_{SW} < \sim 0.5\text{mA}$
- Asymmetric IV may be good
 - Allows larger hysteresis loop
- Non-linear IV may be good
 - Allows larger R_{MTJ} , I_{SW}



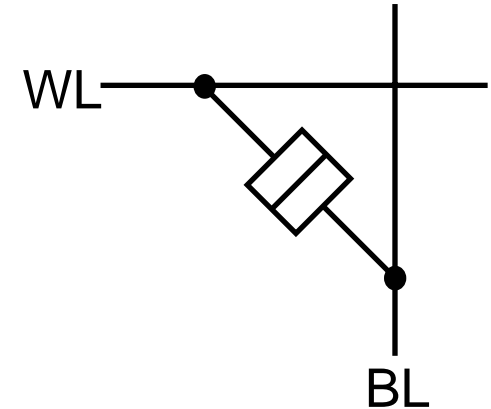
2T1MTJ Array Architecture

- Use CMOS transfer gate ($W_P/W_N = 2.0\lambda m/1.0\lambda m$)
- More symmetric switching at cost of density - still denser than SRAM
- $V_{SW} < V_{DD}$, $I_{SW} < \sim 0.5mA$
- Non-linear IV may be good
 - Allows larger R_{MTJ} , I_{SW}
- Attractive for learning vehicle?



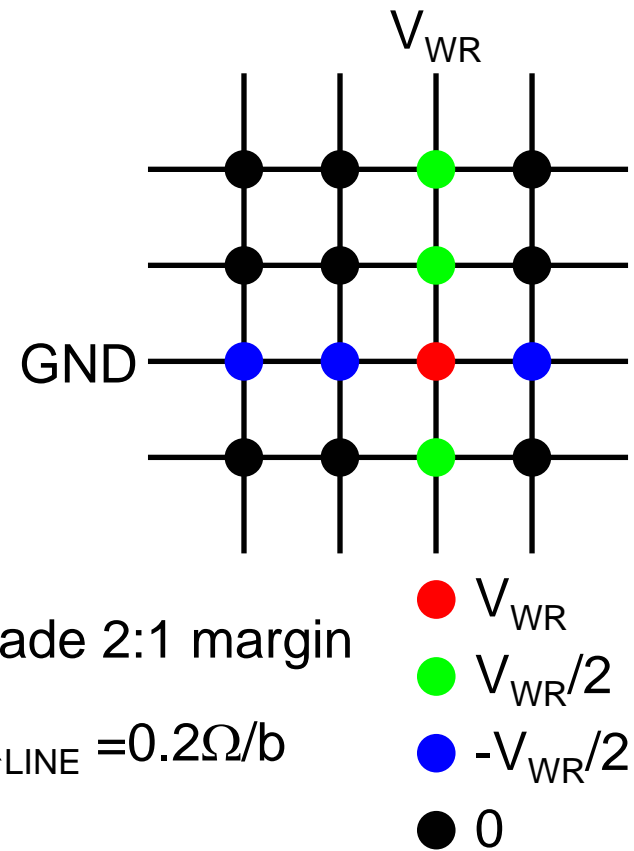
Cross-Point Array Architecture

- MTJ at each intersection of BL & WL
- The “Holy Grail” of memory array architectures
 - Dense - No FET to limit cell size
 - Stackable - Reduce cell size by $1 / \#$ layers
 - Place circuits below array
- “Many have died seeking the Grail...”
 - Poor selection mechanisms for read / write



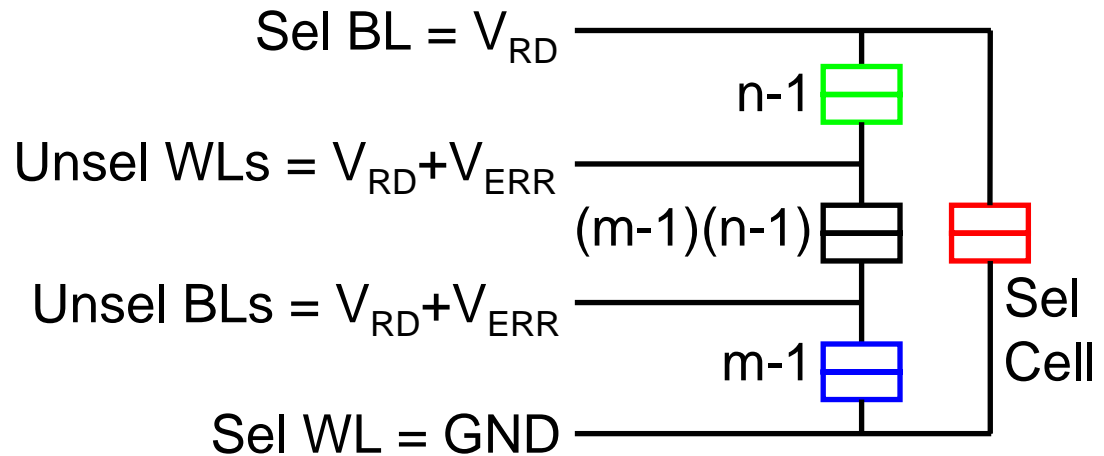
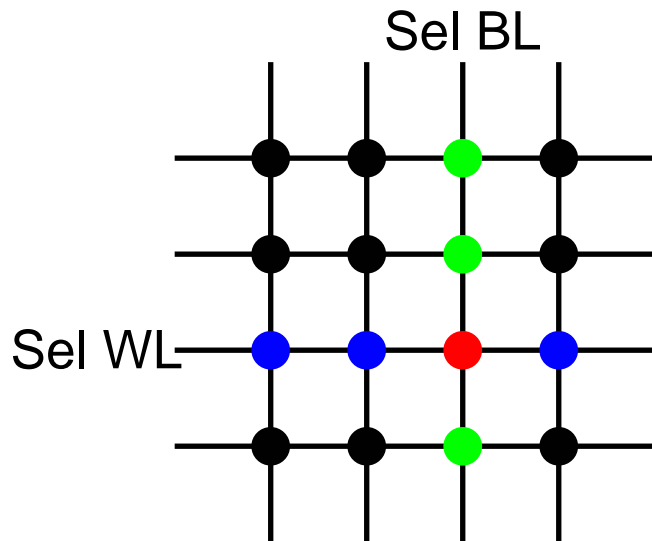
Cross-Point Write

- Unselected BLs, WLs = $V_{WR}/2$
- Selected BL / WL = GND / V_{WR} or V_{WR} / GND
- Selected bit sees $\pm V_{WR}$, half-selected $\pm V_{WR}/2$
- 2:1 voltage margin - not bad
- Half-selected cell currents ● ● must not create:
 - Large IR drops along selected WL / BL - degrade 2:1 margin
 - $R_{MTJ} \gg 1.6K\Omega$ for linear IV, 128 b/line, $R_{LINE} = 0.2\Omega/b$
 - Excessive write power
 - Could lose power advantage over conventional MRAM
 - $I(V_{WR}/2) = 40\lambda A$, 128b/line ~ conventional MRAM at 5mA
- Non-linear IV may be good for reducing half-selected cell currents



Cross-Point Read

- Selected BL = V_{RD} , selected WL = GND, unselected WLS & BLs = $V_{RD} + V_{ERR}$
- BL half-selected current ● < signal current
 - $V_{ERR} < 0.4\text{mV}$ for linear IV, $V_{RD} = 250\text{mV}$, $MR = 40\%$, 128b/BL
 - Must use offset-compensating techniques - complex, slow
 - Or use very non-linear device to reduce $I(V = \pm \text{a few mV})$
- WL half-selected current ● must not create large IR drop along selected WL
 - $R_{MTJ} > 8\text{K}\Omega$ for 128b/WL, $R_{WL} = 0.2\Omega/\text{b}$, $MR = 40\%$ - even slower



Summary

- Spin-switching an attractive candidate for “2nd generation” MRAM
 - Potential advantages in power, write margin, process cost, density
- Simple, fast sensing requires $MR > \sim 10\%$, $V_{RD} > \sim 100\text{mV}$ plus margin
- Additional device requirements based on array architecture:
 - 1T1MTJ / 2T1MTJ
 - At read conditions, $R_{MTJ} \gg R_{FET}$ ($\sim 1\text{K}\Omega$) to avoid effective MR loss
 - Write currents limited by FET to $I_{SW} < \sim 0.5\text{mA}$
 - 2T1MTJ allows more symmetric switching at cost of density
 - Cross-point
 - Half-selected write & read currents create serious problems for:
 - Write margin, write power, read margin

Acknowledgements

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References

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